

UV Nanosecond Laser

HL SERIES

HL-NS-355-30(M)-S



With the unique 'cold processing advantage' of UV light, it is widely used for cutting, drilling, marking and etching of materials in the high-end market of ultra-fine processing.

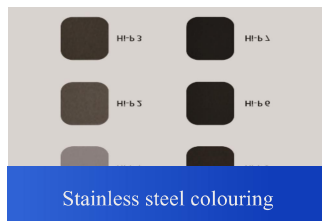
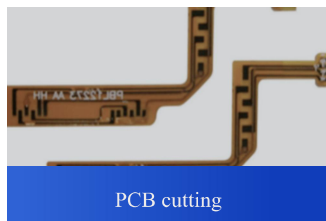
► Application

- Modular design for easy upgrade and maintenance
- TEM₀₀ mode output
- Adjustable repetition rate

► Features

- PCB/FPC board marking, cutting and drilling
- Solar cell process
- Ink removal, PVD layer removal
- Scribing, cutting and drilling of ceramics
- Wafer scribing

► Sample Display



Technical Parameters

HL-NS-355-30(M)-S

Optical Parameters

Wavelength	355 nm
Max. Power	30W@80kHz
Repetition Rate	70kHz~200kHz
Pulse Width	20ns-100ns
Pulse Energy Stability (rms)	< 3% rms@80kHz
Power Stability	< 2% rms

Beam Characteristics

Spatial Mode	TEM ₀₀
Beam Quality	M ² < 1.3
Polarization Ratio	> 100:1(horizontal)
Beam Diameter at Exit	1.4mm ± 0.2mm
Divergence Full Angle (1/e ²)	< 2 mrad
Circularity	> 90%
Beam Pointing Stability	≤ ±25 μrad/°C

Working Conditions

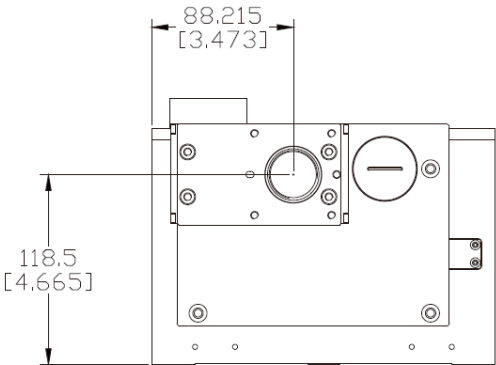
Power Supply	36VDC±1V; ≥600W switching power supply
Warm-up Time	Standby to ready < 10 minutes; cold start to readiness < 30 minutes
Temperature Range	15~30°C during working hours; 0~50°C during non-working hours
Temperature Range	10~70%, non-condensation
Cooling Requirements	Water cooling, cooling capacity ≥ 100W, accuracy ± 0.1°C, flow rate ≥ 10L/min

Physical Properties

Laser Dimensions	698mm×214mm×165.9mm (L x W x H)
Laser Weight	32 kg

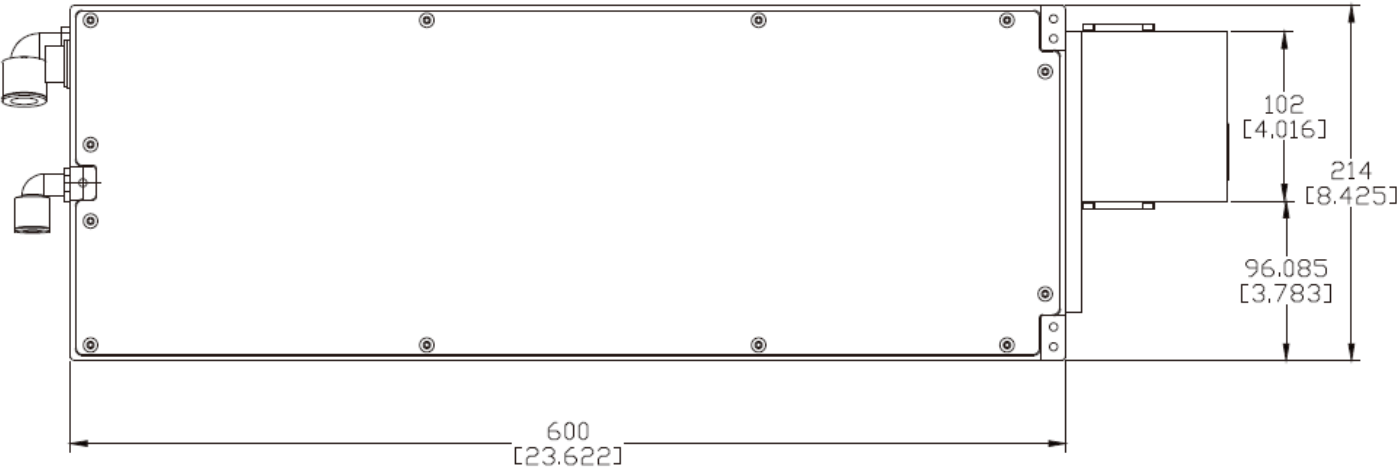
► All specifications are typical data and subject to change without notice due to product improvements.

Laser Dimensions (mm)



Front View

Bottom View



Side View

